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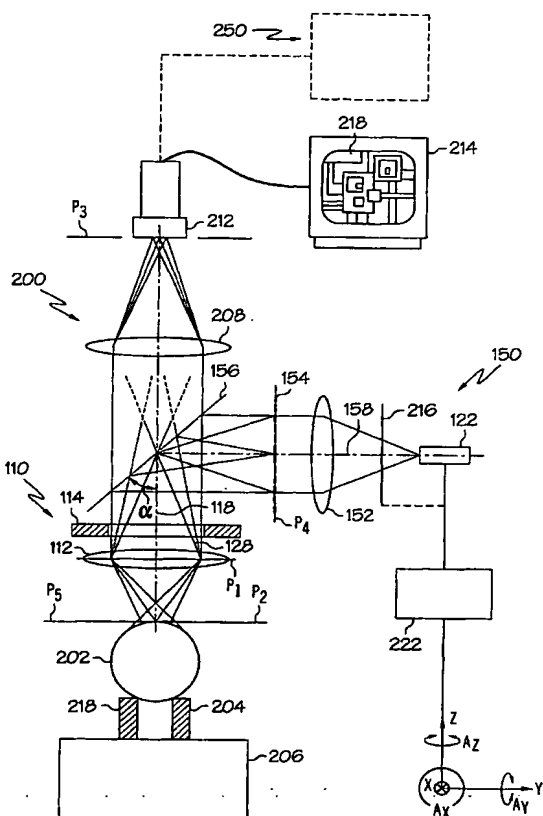
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(54) Title: SYSTEM AND METHOD FOR DETECTING AND CORRECTING POSITION DEVIATIONS OF AN OBJECT HAVING A CURVED SURFACE



(57) Abstract—A position deviation system (10) and method detects and corrects position deviations between the optical axis (118) of an optical system (100), such as an exposure apparatus (150), and the center of a curved shaped object, such as a spherical shaped semiconductor. The system determines position deviations by illuminating the curved surface (124), passing light that is reflected off of the illuminated curved surface (124) through a first lens (112) having an optical axis (118) and a first body. An image having a substantially central portion is formed on a surface using the reflected light. The position deviation is determined based on a position of the substantially central portion of the formed image relative to the optical axis (118).